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高密度氧化铟锡(ITO)靶材的制备研究

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Study on the preparation of ITO ceramic target with high density

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摘要 以水热合成的2种不同粒径(70 ± 8)nm和(40 ± 6)nm单分散ITO粉末为原料,对原料粉体粒径分布、冷等静压成型压力、烧结温度和时间等与靶材烧结密度之间的关系进行了研究.当2种粒径原料按7:3质量比混合均匀,成型压力为250MPa,成型坯体经1300℃预烧1.5h和在1400℃烧结1h后可以得到相对密度大于99%的高密度、高纯度ITO靶材.

关键词: 高密度 ITO 靶材 制备

Abstract: The indium tin oxide(ITO) ceramic target with high relative density was prepared by cold iso-static pressing and sinter at air atmosphere process,using the mono-dispersed ITO powders with two different particle size(70 ± 8)nm and(40 ± 6)nm which synthesized by resin-hydrothermal as raw materials.The factors among the particle size-distribution,pressure and sintering temperature etc which affected the density of ITO ceramic target have been investigated.The ITO ceramic target could have get a relative density about 99.28% by means of which are mixed powder with 7:3 weight ratio and molded under 250MPa of CIP pressure and then sintered at the temperature of 1300℃ for 1.5 h and 1400℃ for 1 h.

Key words: relative density indium tin oxide(ITO) target preparation

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